

Resource Summary Report

Generated by [kravitz2](#) on Jul 28, 2026

JEOL: JBX-8100FS Electron Beam Lithography System

RRID:SCR_020170

Type: Tool

Proper Citation

JEOL: JBX-8100FS Electron Beam Lithography System (RRID:SCR_020170)

Resource Information

URL: <https://www.jeolusa.com/PRODUCTS/Photomask-Direct-Write-Lithography/Electron-Beam-Lithography/JBX-8100FS>

Proper Citation: JEOL: JBX-8100FS Electron Beam Lithography System (RRID:SCR_020170)

Description: Electron beam lithography system that writes ultrafine patterns at faster rate of speed while minimizing idle time, especially during exposure process, thus increasing throughput.

Resource Type: instrument resource

Keywords: Jeol, JEOL, Electron Beam Lithography System, Instrument Equipment, USEDit,

Availability: Commercially available

Resource Name: JEOL: JBX-8100FS Electron Beam Lithography System

Resource ID: SCR_020170

Alternate IDs: Model_Number_JBX_8100FS

Record Creation Time: 20220129T080349+0000

Record Last Update: 20260725T190922+0000

Ratings and Alerts

No rating or validation information has been found for JEOL: JBX-8100FS Electron Beam Lithography System.

No alerts have been found for JEOL: JBX-8100FS Electron Beam Lithography System.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.